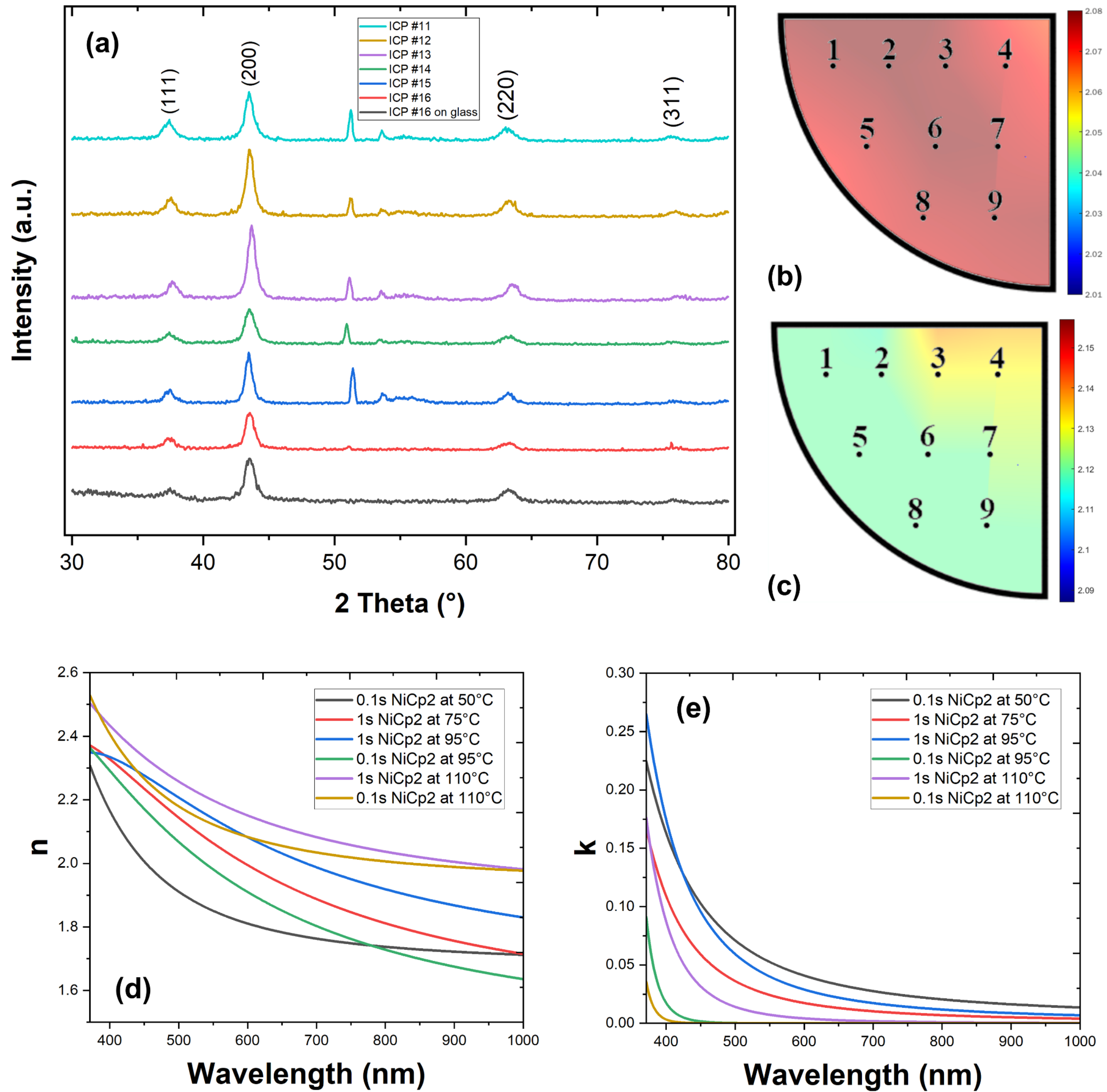

Figure 1: (a) Grazing-incidence XRD of ICP-ALD grown NiO film with 300 W O_2/Ar plasma and 150°C substrate temperature on Si(100) and glass substrates, revealing polycrystalline single-phase cubic NiO (*c*-NiO). (b,c) Multiwavelength ellipsometric sample mapping of the refractive index values obtained from ICP-ALD grown NiO samples: top sample shows NiO uniformity for $NiCp_2$ @ 95 °C, while bottom sample depicts NiO uniformity for $NiCp_2$ @ 110 °C. Spectroscopic ellipsometer measurements of ICP-ALD grown NiO samples: (d) spectral refractive index; (e) spectral extinction coefficient.